

**REMARKS**

Applicants respectfully request reconsideration based on the above amendments and the following remarks. Applicants respectfully submit that the claims as presented are in condition for allowance.

In the claim amendments, claims 1 and 8 have been amended. Support for the amendment can be found in the entire specification. No new matter has been added by the amendments.

Claims 1-4 and 8-15 stand rejected under 35 U.S.C. §103(a) as being unpatentable over Kim (US 2001/0019126) in view of Lee (US 2002/0041347) for the reasons stated on pages 2-4 of the Office Action. Applicants respectfully traverse the rejection.

For an obviousness rejection to be proper, the Examiner must meet the burden of establishing that all elements of the invention are disclosed in the prior art; that the prior art relied upon, coupled with knowledge generally available in the art at the time of the invention, must contain some suggestion or incentive that would have motivated the skilled artisan to modify a reference or combined references; and that the proposed modification of the prior art must have had a reasonable expectation of success, determined from the vantage point of the skilled artisan at the time the invention was made. *In re Fine*, 5 U.S.P.Q.2d 1596, 1598 (Fed. Cir. 1988); *In Re Wilson*, 165 U.S.P.Q. 494, 496 (C.C.P.A. 1970); *Amgen v. Chugai Pharmaceuticals Co.*, 927 U.S.P.Q.2d, 1016, 1023 (Fed. Cir. 1996). Kim or Lee neither teaches nor suggests all elements of the invention for the following reasons.

The Examiner has stated on page 4 of the final office action that the transparent pixel electrode layer (44b in Fig. 15) of Kim is in deed in contact with an upper surface of a side surface of the second conductive film (32) in the contact hole, and that it is noted the term of "an upper surface" of a film does not have to be interpreted as meaning: the top surface of the film. On the contrary of the Examiner's interpretation with respect to the term of "an upper surface", the IZO layer disclosed in the claimed invention contacts the top surface of the upper film through the contact hole. Figure 1B of the application, for example, shows that the top surface of the upper film 72q is contact with the IZO layer 76.

Best Available Copy

Therefore, claim 1 recites a contact structure of a semiconductor device, the contact structure comprising: a dry-etchable lower conductive film; an upper conductive film formed on the lower film and including Al or Al alloy, the upper film having edges located on the lower film; an insulator having a contact hole exposing at least a portion of the lower film; and an IZO layer formed on the insulator and contacting the lower film and a top surface of the upper film through the contact hole.

In contrary, the gate pad 44b disclosed in the figure 15 of Kim does not contact the top surface of the second gate layer 32. Therefore, Kim neither teaches nor suggest the feature "an IZO layer formed on the insulator and contacting the lower film and a top surface of the upper film through the contact hole", as recited in claim 1. The deficiency of Kim is not cured by Lee, because Lee neither teaches nor suggests the feature "an IZO layer formed on the insulator and contacting the lower film and a top surface of the upper film through the contact hole", as recited in claim 1. Accordingly, the combination of Kim and Lee does not render claim 1 obvious, because none of them teaches or suggests the feature "an IZO layer formed on the insulator and contacting the lower film and a top surface of the upper film through the contact hole", as recited in claim 1.

Since it contains similar features, claim 8 is believed to allowable for at least the reasons given for claim 1. Claims 2-4 depend from claim 1, and claims 9-10 and 12-15 depend from claim 8. These dependent claims are believed to be allowable due to their dependency on claims 1 and 8.

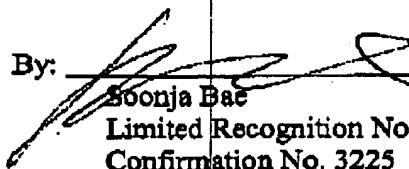
In view of the foregoing, it is respectfully submitted that the instant application is in condition for allowance. Accordingly, it is respectfully requested that this application be allowed and a Notice of Allowance issued. If the Examiner believes that a telephone conference with Applicants' attorneys would be advantageous to the disposition of this case, the Examiner is cordially requested to telephone the undersigned.

In the event the Commissioner of Patents and Trademarks deems additional fees to be due in connection with this application, Applicants' attorney hereby authorizes that such fee be charged to Deposit Account No. 06-1130.

DO NOT FILE COPY

Respectfully submitted,

CANTOR COLBURN LLP

By: 

Soojae Bae  
Limited Recognition No. L0017  
Confirmation No. 3225  
Cantor Colburn LLP  
55 Griffin Road South  
Bloomfield, CT 06002  
PTO Customer No. 23413  
Telephone: (860) 286-2929  
Facsimile: (860) 286-0115

Date: June 20, 2005

Best Available Copy